



Docket No.: 0171-1100PUS1
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**In re Patent Application of:
Takeru WATANABE et al.**

Application No.: 10/849,186

Confirmation No.: 7245

Filed: May 20, 2004

Art Unit: 1752

**For: BASIC COMPOUND, RESIST COMPOSITION
AND PATTERNING PROCESS**

Examiner: J. S. Y. Chu

REPLY TO RESTRICTION REQUIREMENT

**Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450**

Sir:

In reply to the Restriction Requirement dated June 10, 2005, the following remarks are respectfully submitted in connection with the above-identified application.

This reply includes: amendments to the claims and Remarks.

the compounds of Group III. Whatever, the position of the Examiner as to Group II, all claims of both Groups I and III should be examined.

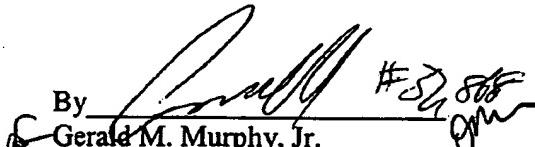
Summary

Should there be any outstanding matters that need to be resolved in the present application, the Examiner is respectfully requested to telephone David R. Murphy (Reg. No. 22,751) at 703-205-8000; Extension 8053 to conduct an interview in an effort to expedite prosecution of this case.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§ 1.16 or 1.17; particularly, extension of time fees.

Dated: June 29, 2005

Respectfully submitted,

By 
Gerald M. Murphy, Jr.
Registration No.: 28,977
BIRCH, STEWART, KOLASCH & BIRCH, LLP
8110 Gatehouse Rd
Suite 100 East
P.O. Box 747
Falls Church, Virginia 22040-0747
(703) 205-8000
Attorney for Applicant